



CFD Based Researches and Applications for Fluid Machinery and Fluid Device

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submissions:

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Message from the Guest Editors

Dear Colleagues,

The demand for computational fluid dynamics (CFD)-based numerical techniques is increasing rapidly with the development of the computing power system. These advanced CFD techniques are applicable to various issues in the industrial engineering fields and especially contributing considerably to the design of fluid machinery and fluid devices, which have very complicated unsteady flow phenomena and physics.

This Special Issue on “CFD-Based Research and Applications for Fluid Machinery and Fluid Devices” aims to present recent novel research trends based on advanced CFD techniques for fluid machinery and fluid devices. The following topics, among others, are included in this issue:

- CFD techniques and applications in fluid machinery and fluid devices;
- Unsteady and transient phenomena in fluid machinery and fluid devices;
- Pumps, fans, compressors, hydraulic turbines, pump-turbines, valves, etc.





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Message from the Editor-in-Chief

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